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U.S. PATENT DOCUMENTS

Examiner
initials
for this
application

EXAMINER INITIALS	DOCUMENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPR.
JPB	4,256,828	3/17/81	George H. Smith	430	280.1	
PRM	4,882,245	11/21/89	Jeffrey D. Gelorme, et al.	430	280.1	
JPB	4,940,651	7/10/90	Lawrence M. Brown, et al.	430	280.1	
MEM	5,026,624	6/25/91	Richard A. Day, et al.	430	280.1	
JJS	5,043,221	8/27/91	Joseph V. Koleske	428	413	
CH	5,098,616	3/24/92	Edward D. Babich, et al.	430	280.1	
MEM	5,102,772	4/7/92	Raymond W. Angelo, et al.	430	280.1	
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SR	5,859,655	1/12/99	Jeffrey Donald Gelorme, et al.	204	501	

FOREIGN PATENT DOCUMENTS

EXAMINER INITIALS	DOCUMENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES NO

OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)

Crivello et al. "Photoinitiated Cationic Polymerization with Triarylsulfonium Salts", Journal of Polymer Science: Polymer Chemistry Edition, Vol. 17, pp. 977-999 (1979).

N. La Branca and J.D. Gelorme, "High Aspect Ratio Resist for Thick Film Applications", Proc. SPIE, Vol. 2438, pp. 846-852 (1995).

K.Y. Lee et al., "Micromachining applications of a high resolution ultrathick photoresist", J. Vac. Sci. Technology B 13(6), Nov./Dec. 1995.

Sotec Microsystems Photoepoxies Product Brochure

EXAMINER: *Cy M. Hunter* DATE CONSIDERED: 02-9-03

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.